

**AMENDMENTS TO THE ABSTRACT:**

Please amend the abstract as follows:

**Abstract**

A17  
The batch projection regions 13 and 14 of ~~the~~ an electron beam projection mask are arranged so that pattern density may be equalized on the whole wafer surface.--

**HAYES SOLOWAY P.C.**

130 W. CUSHING ST.  
TUCSON, AZ 85701  
TEL 520 882 7623  
FAX 520 882 7643

175 CANAL STREET  
MANCHESTER, NH 03101  
TEL 603 668 1400  
FAX 603 668 8567